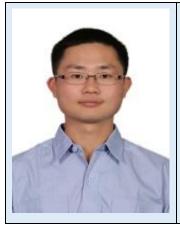
## 師資介紹



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B. Journal Paper - EI (期刊論文)

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- C46. <u>顏志峰</u>\*、王孝婕, "工廠自動化系統應用於製程檢驗之效益分析與探討",2022 第二十屆微電子技術發展與應用研討會,高雄,台灣,16頁,中華民國一百一十一年五月二十日

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- D. Patent (專利)
- D1. 李明逵、黃俊杰和<u>顏志峰</u>,"一種高介電常數與低漏電流磷化銦金氧半電容的製作方法",中華民國,發明專利第 I 249841 號
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- E. 執行研究計畫
- E1. 以超薄 LPD-SiON/非真空式 ALD-TiO<sub>2</sub> 為閘極氧化層之增強型 N 通道磷化銦電晶體製作,104-2221-E-022-016-
- E2. 以非真空式原子層沉積技術研製具高品質超薄氧化鋁/二氧化鈦/氧化鋁閘極氧化層之磷化銦金氧半場效電晶體, 103-2221-E-451-012-